

Upgrading Wolter Imagers for X-Ray Diagnostics in the Z Pulsed-Power Facility at Sandia National Laboratories

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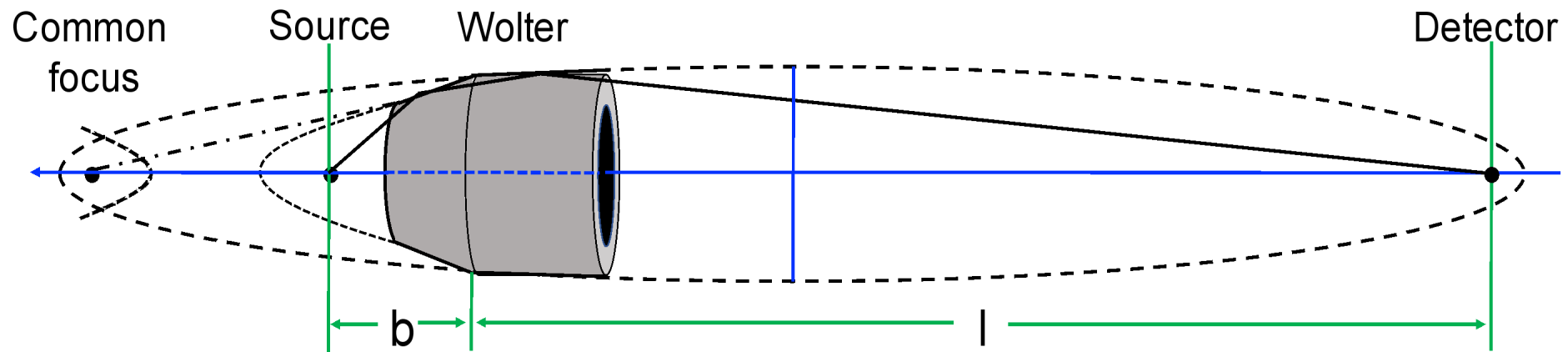
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HTPD 2020, Virtual Meeting, Dec 14-17, 2020



Operation Principle of Wolter Optics

- Three families of designs, nestable version (Wolter I) most widely used
- Wolter I has properties similar to a thin lens
- Wolter design addresses two challenges of grazing-incidence optics
 - Nested designs allow for increased collecting efficiency
 - Two conic surfaces of revolutions nearly satisfy Abbe sine rule reducing strongest aberration contributions



Major advantages of Wolters include:
large solid angle, large field of view (FoV), large throughput



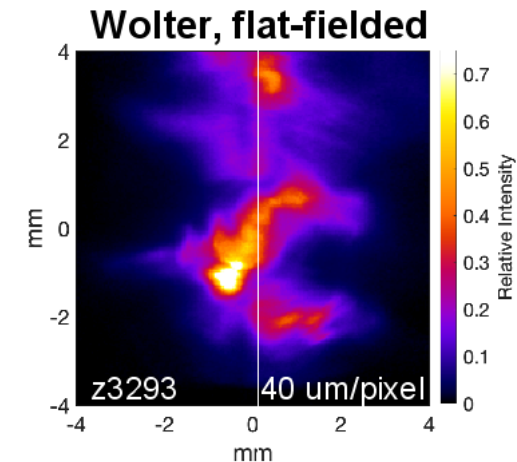
Z-Wolter Optics Performance

Wolter imager successfully fielded in SNL's Z machine

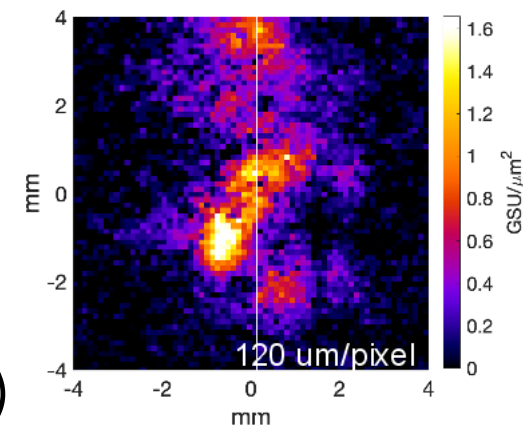
- K-shell emission data using Mo wire arrays (~ 17.5 keV) demonstrated superior imaging capability over large field of view ($5 \times 5 \text{ mm}^2$) enabling in-depth study of these sources
- Improvement in signal of factor 100-1000 compared to pinhole camera image in same E-range
- Wolter optic reveals features of order $< 200 \mu\text{m}$

Extending Wolter applications for future experiments

- Temporally-resolved imaging (photon starvation)
- Higher energies (dimmer sources/need high reflectivity R)
- Better spatial resolution (challenges for optics fabrication)



Pinhole camera, 17 – 18 keV



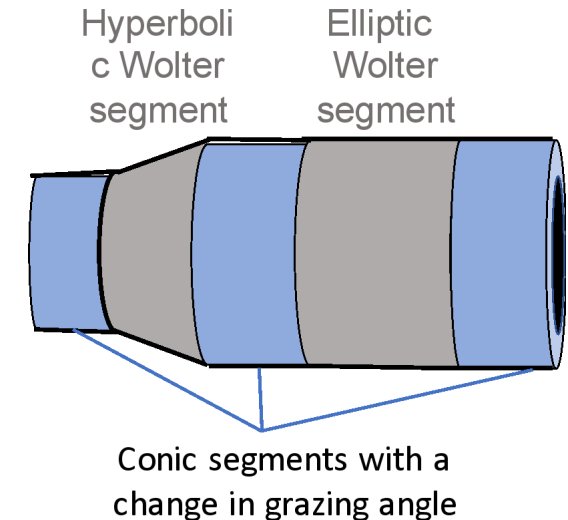
Next generation of Wolter imaging diagnostics requires high throughput and ideally further improved spatial resolution (< 50 microns)



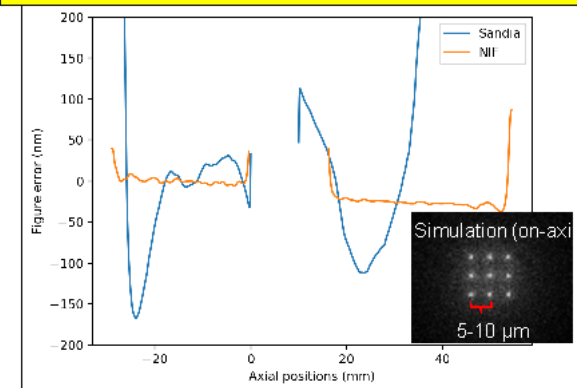
Improvements for Next-Gen Wolter Optics

1) Fabrication of High-Precision Mandrel

- Design improvements for mandrels: flat segments added to mitigate performance-degrading end-effects
- Polishing procedure improved to produce more consistent surface: Upgraded polishing slurry & alignment procedure for sub-aperture polisher (Zeeko)
 - 2× decrease in figure error & reduced process time
- MSFC IXPE (Imaging X-ray Polarimetry Explorer) optic required improved lap polishing directly benefitting NIF/Z Wolter
 - Error introduced during polishing reduced by a factor of ~5 with new process
- Improvements enabled fabrication of test mandrel meeting NIF figure requirement to achieve <5-10 μm resolution over 1 mm FoV (10× reduction in figure error)



Optical profilometer measurement of mandrel figure error for 1st gen Z-Wolter and 2nd gen NIF-Wolter

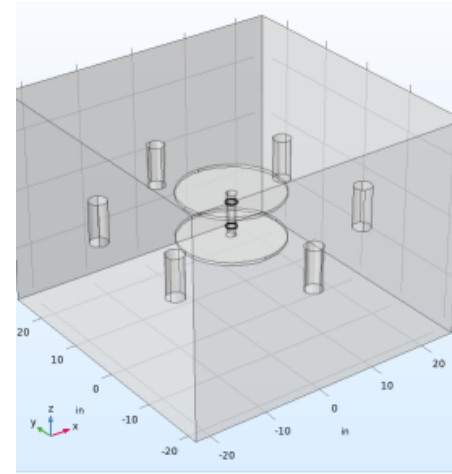


Improved Lap polishing and Zeeko able to maintain figure and roughness to provide mandrel expected to produce shells for <50 μm spatial resolution on Z

Improvements for Next-Gen Wolter Optics

2) Advancing Replication Technology

- Improved fast ($<1\text{h}/\text{shell}$) metrology setup using IXPE assembly station
 - Shells suspended from 3 wires
 - Enables measurements along length of shell and multiple azimuthal positions
 - First results indicate end-effect deformations restricted to flat pieces ($4\text{--}8\text{ }\mu\text{m}$ peak-to-valley); optic largely unaffected



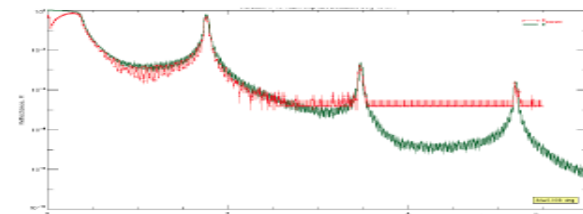
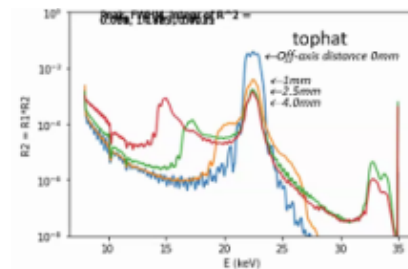
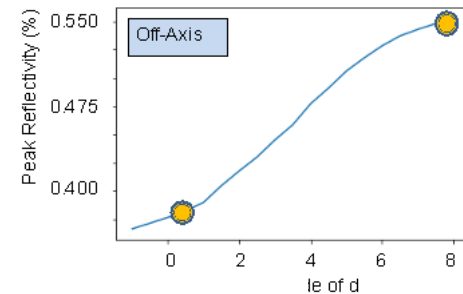
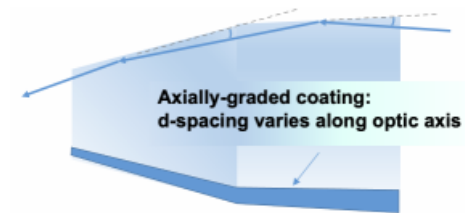
- Comsol 3D simulations of replication bath to determine key factors to improve deposition uniformity
 - Geometric dimensions
 - Electrolyte conductivity
 - Gasket configuration and copper tape usage
- Replication tests planned to verify model predictions
- Plans to include effects causing non-symmetric azimuthal variations

Focus on improving replication process to keep additional figure error contributions from replication and release small and use full potential of mandrel

Improvements for Next-Gen Wolter Optics

3) Boosting Multilayer Reflectivity

- Optimization of multilayer (ML) recipes using evolved search algorithms for constant d-spacing, multiple-stack and depth-graded designs
 - Study showed axial ML grading of about 6% could further increase reflectivity by 1.4×
 - Optimization for best performance and maximal flexibility: highest reflectivity, flat response, optimal rejection of photons outside of spectral ROI (non-thermal vs thermal)
- Advancing multilayer deposition process
 - Push reflectivity by increasing number of deposited layer pairs via higher operating current of coater
 - Improvements to coating uniformity possible using coating mask
 - Exploring additional options to boost reflectivity
 - Use of alternative ML material systems
 - Reactive sputtering to increase R and reduce stress



Conclusions and Outlook

- Wolter optics successfully employed in SNL's Z-machine:
Improvement in signal-to-noise of factor ~ 10 -30 compared to current best diagnostic and reached 60-300 μm spatial resolution (previously 900 μm)
- Pushing technologies to higher spatial resolutions ($< 50 \mu\text{m}$ for Z, < 5 -10 μm for NIF) with R&D on mandrel fabrication and polishing as well as replication
- Implementation of time-gated imaging has highest priority together with longer-term goal of pushing Wolter application towards higher energies both require boosting the reflectivity

**For more information please attend Jeff Fein's invited talk:
High-resolution imaging of warm x-ray sources with a Wolter optic on the Z Machine
or feel free to contact me (vogel9@llnl.gov)**



THANK YOU FOR YOUR ATTENTION!

QUESTIONS?



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